

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office



Atty.
Dkt. No.

M#

Client Ref.

0306781

P-0381.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: LOF et al.

Appln. No.: 10/705,805

Filing Date: November 12, 2003

Examiner: Unknown

Group Art Unit: 1756

Date: January 6, 2005

Page 1 of 1

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Examiner's Initials	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
PK	AR 4,390,273	06/1983	LOEBACH et al.	355	125	
	BR 2004/0109237 A1	06/2004	EPPLE et al.			
	CR 6,236,634 B1	05/2001	LEE et al.	369	112	
	DR 2002/0020821 A1	02/2002	VAN SANTEN et al.	250	492	
PK	ER 2004/0119954	06/2004	KAWASHIMA et al.	355	30	
	FR 2004/0125351	07/2004	KRAUTSCHIK	355	53	
	GR					
	HR					

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					Enclosed	No	Enclosed	No
PK	IR JP 11-176727	07/1999	JAPAN	SHIRAISHI	X			
	JR JP 2000-058436	02/2000	JAPAN	FUJISHIMA et al.	X			
	KR WO 2004/053950 A1	06/2004	PCT	OWA	X			
	LR WO 2004/053951 A1	06/2004	PCT	MAGOME et al.	X			
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	NR WO 2004/053953 A1	06/2004	PCT	NEI et al.	X			
	OR WO 2004/053954 A1	06/2004	PCT	NEI et al.	X			
	PR WO 2004/053955 A1	06/2004	PCT	HIRUKAWA et al.	X			
	QR WO 2004/053956 A1	06/2004	PCT	NAGASAKA et al.	X			
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	SR WO 2004/053958 A1	06/2004	PCT	MIZUTANI et al.	X			
	TR WO 2004/053959 A1	06/2004	PCT	SHIRAI	X			
	UR WO 2004/053596 A2	06/2004	PCT	GRAUPNER	X			
	VR WO 2004/055803 A1	07/2004	PCT	VAN SANTEN	X		X	
	WR WO 2004/057589 A1	07/2004	PCT	NEIJZEN et al.	X		X	
	XR WO 2004/057590 A1	07/2004	PCT	VAN SANTEN et al.	X		X	
PK	YR JP 2004-193252	07/2004	Japan	Not Available	X			
	ZR							
	AAR							

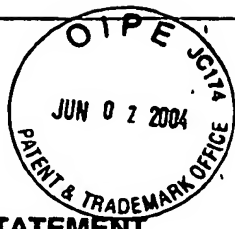
OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

BBR								
CCR								
DDR								
EER								
FFR								

Examiner

Date Considered:

*EXAMINER: initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.



Atty. Dkt. No.	M#	Client Ref.
	306781	P-0381.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: LOE et al.
Appln. No.: 10/705,805
Filing Date: November 12, 2003
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Group Art Unit: 1756

Date: June 2, 2004 Page 1 of 1

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ML	AR 2004/0075895 A1	04/2004	LIN			
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	CR					
	DR					
	ER					
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	HR					

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	Document Number	Date MM/YYYY	Country	Inventor Name		English Abstract		Translation Readily Available	
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	JR JP 58-202448	11/1983	JAPAN	KAWAMURA et al.	X				
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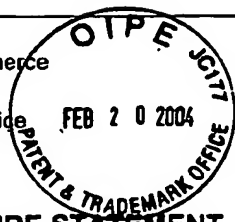
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	SR	H. HATA, "The Development of Immersion Exposure Tools", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-22			
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	UR	"Depth-of-Focus Enhancement Using High Refractive Index Layer on the Imaging Layer", IBM Technical Disclosure Bulletin, Vol. 27, No. 11, April 1985, p. 6521			
	VR	A. SUZUKI, "Lithography Advances on Multiple Fronts", EEdesign, EE Times, January 5, 2004			
PL	WR	B. LIN, "The k_3 coefficient in nonparaxial λ/NA scaling equations for resolution, depth of focus, and Immersion lithography, J. Microlith., Microfab., Microsyst. 1(1):7-12 (2002)			
	XR				
	YR				
	ZR				

Examiner *P. B. [Signature]* Date Considered: 3/18/05

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: Joeri LOF et al.

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Date: February 20, 2004

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of

1

Examiner: Unassigned

Group Art Unit: Unassigned

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	KR					
	LR					
	MR					
	NR					

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	OR									
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	RR									
	SR									
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	AAR				
	BBR				
	CCR				
	DDR				

Examiner

[Signature]

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